

U.S. Department of Commerce, Patent and Trademark				Atty. Docket No.		Application No.	
INFORMATION DISCLOSURE STATEMENT BY REQUESTOR				SENS.005US1		10/685,550	
				Applicant(s)		Conf. No.	
(Use several sheets if necessary)				Wayne G. Renken		4924	
				Filing Date		Group	
				October 14, 2003		2856	

U.S. Patent Documents							
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	

U.S. Published Patent Application Documents							
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
SS	1	2002/0078770	Jun. 27, 2002	Hunter			
SS	2	2002/0148307	Oct. 17, 2002	Jonkers			

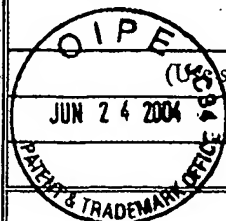
Foreign Patent Documents								
							Translation	
	Document	Date	Country	Class	Subclass	Yes	No	
SS	3	WO 03/067183	Aug. 14, 2003	WIPO				

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)		

Examiner <i>Sauif Shd</i>	Date Considered <i>8/8/2007</i>
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.

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88	27	EP 1014437 A2	Jun. 28, 2000	Europe				
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88	30	Prov. Pat. App. No. 60/285,613 filed 4/19/01; Freed et al.; "Firmware, Methods, Apparatus, and Computer Program Products for Wafer Sensors"						
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